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(54)	MICROELECTRONIC DEVICE
	COMPRISING LARGE CONTACT SURFACES
	BETWEEN THE CONDUCTION CHANNEL
	AND THE SOURCE AND DRAIN REGIONS

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(57)ABSTRACT

A microelectronic device comprising:

- a semiconductor layer (120) several first areas (122) of which are superposed and form a channel;
- an electrostatic control gate (110) and a gate dielectric layer (112) or a ferroelectric memory layer (112) parts of which are each arranged between a part (106, 108) of the gate and one amongst the first areas;
- dielectric spacers (114) arranged against sidewalls of the gate;

source (116)/drain (118) regions electrically coupled to the first areas by second areas (124) of the semiconductor layer extending between the source/drain regions and the spacers, and/or between a substrate (102) and each of the source/drain regions; and wherein the second areas are not arranged directly against the layer and form a continuous layer with the first areas.

